

IN THE CLAIMS:

Please cancel Claims 3-17 without prejudice or disclaimer of the subject matter recited therein.

Please amend Claims 1, 2 and 18-22 and add new Claims 23-28 as follows.

1. (Currently Amended) A method of manufacturing a ~~mask dot pattern~~, comprising the steps of:

preparing a structured material ~~comprising~~ composed of a plurality of columnar members ~~and a region containing a first component and a region containing a second component different from the first component~~ surrounding the columnar members, the structured material being formed by depositing the first component and the second component on a substrate;

removing the columnar members from the structured material to form a porous material having a columnar hole; ~~and~~

introducing a mask material into the columnar hole of the porous material to form a dot pattern; and

removing the porous material.

2. (Currently Amended) The method of manufacturing a ~~mask member dot pattern~~ according to claim 1, ~~wherein the columnar members of the structured material which are so formed as to contain a first material are surrounded by the region which is so formed as to~~

contain a second material, and wherein the second material component is contained at a ratio of not less than 20 atomic% and not more than 70 atomic% with respect to the total amount of the first material component and the second material component.

Claims 3-17. (Cancelled).

18. (Currently Amended) A method of manufacturing a columnar structured material using a dot pattern manufactured by the method according to claim 1, and further comprising:

~~a step of preparing, on a substrate, a structured material in which columnar substances which are so formed as to contain a first component are dispersed in a member which is so formed as to contain a second component that can form a eutectic together with the first component;~~

~~a removal step of removing the columnar substances;~~

~~an introducing step of introducing a mask material into columnar holes of a porous material having the columnar holes obtained through the removal step;~~

~~a step of preparing dots made of the mask material by removing the member;~~

~~a step of etching the substrate with the dots dot pattern as a mask; and~~

~~a step of removing the dots dot pattern.~~

19. (Currently Amended) The method of manufacturing a ~~columnar structured material~~ dot pattern according to claim ~~18~~ 1, wherein the ~~removal~~ removing step of removing the columnar substances members is an etching step.

20. (Currently Amended) The method of manufacturing a ~~columnar structured material~~ dot pattern according to claim ~~18~~ 1, wherein the introducing step of introducing a ~~mask~~ the material into the holes is an electrodeposition step.

21. (Currently Amended) The method of manufacturing a columnar structured material according to claim 18, wherein the step of etching the substrate with the ~~dots~~ dot pattern as a mask is a dry etching step.

22. (Currently Amended) The method of manufacturing a ~~mask member~~ dot pattern according to claim 1, wherein the ~~mask~~ material contains a noble metal.

23. (New) The method of manufacturing a dot pattern according to claim 1, wherein the first component and the second component form a eutectic system.

24. (New) The method of manufacturing a dot pattern according to claim 1, wherein the second component is contained at a ratio of not less than 30 atomic% and not

more than 60 atomic% with respect to the total amount of the first component and the second component.

25. (New) The method of manufacturing a dot pattern according to claim 1, wherein the plurality of columnar members are crystalline aluminum columns.

26. (New) The method of manufacturing a dot pattern according to claim 1, wherein the region is composed of an amorphous $\text{Si}_x\text{Ge}_{1-x}$ ($0 < x < 1$).

27. (New) The method of manufacturing a dot pattern according to claim 1, wherein the deposition of the first component and the second component is performed by a sputtering method.

28. (New) A method of manufacturing a dot pattern, comprising the steps of:

preparing a structured material composed of a plurality of columnar members containing a first component and a region containing a second component different from the first component surrounding the columnar members, the structured material being formed by sputtering the first component and the second component on a substrate;

removing the columnar members from the structured material to form a porous material having a columnar hole;

introducing a material into the columnar hole portions of the porous material to form a dot pattern ;and

removing the porous material.